

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

PATENT

In re application of: PATRICK et al.

Attorney Docket No.:
LAM1P061/P0318

Application No.: 08/925,985

Examiner: MARKOFF, A.

Filed: September 9, 1997

Group: 1746

Title: APPARATUS FOR IMPROVING ETCH
UNIFORMITY AND METHODS
THEREFOR

CERTIFICATE OF EXPRESS MAILING

I hereby certify that this paper is being deposited with the United States Postal Service on May 12, 2000, in an envelope as "Express Mail Post Office to Addressee" service under 37 CFR §1.10, Mailing Label EL769088553US, addressed to: Box CPA, Assistant Commissioner for Patents, Washington, D.C. 20231.

Signed: _____

Alison Gates

PRELIMINARY AMENDMENT

Assistant Commissioner for Patents
Washington, D.C. 20231

Dear Sir:

In response to the Office Action dated December 5, 2001, please amend the above-identified patent application as follows:

In the Claims:

Please amend claims 9 and 30.

All pending claims have been reproduced below for the convenience of the Examiner. Claims which have been changed by this amendment are indicated with an asterisk ("*").

1. (Thrice Amended) In a plasma processing chamber, a method for improving etch uniformity while etching a semiconductor substrate, comprising:

placing said semiconductor substrate into a sacrificial substrate holder, said sacrificial substrate holder being configured to present a sacrificial etch portion surrounding said semiconductor substrate to a plasma within said plasma processing chamber to permit said